

SPECIFICATION AMENDMENTS

Pages 35-36, bridging paragraph:

--As the tin compound used in the gas material for forming a medium refractive index layer useful for the present Invention, there are an organic tin compound, a tin hydride compound and a tin halide. Examples of the organic tin compound include dibutyldiethoxytin, butyltin tris (2,4-pentanedionato), tetraethoxytin, methyltriethoxytin, diethyldiethoxytin, triisopropylethoxytin, ethylethoxytin, methylmethoxytin, isopropylisopropoxytin, tetrabutoxytin, diethoxytin, dimethoxytin, diisopropoxytin, dibutoxytin, dibutyryloxytin, diethyltin, tetrabutyltin, tin bis(2,4-pentanedionato), ethyltin acetoacetonato, ethoxytin (2,4-pentanedionato), dimethyltin (2,4-pentanedionato), diacetomethylacetatotin, diacetoxytin, dibutoxydiacetoxytin, and diacetoxytin diacetoacetonato. Examples of the tin halide include tin dichloride and tin tetrachloride. These compounds can be preferably used in the present invention. The tin compound layer is also useful for an antistatic layer, since its surface resistivity can be reduced to not more than $10^{11} \Omega/\text{cm}^2$

sq.

Table 1

Sample No.	Trans-mittance (%)	Volume Resistivity ($\times 10^{-4}$ $\Omega \cdot \text{cm}^3$)	Etching Property	Remarks
Sample 11	95	2.1	A	Inv.
Sample 12	96	2.9	B	Inv.
Sample 13	91	40.0	F	Comp.
Sample 14	92	98.0	F	Comp.
Sample 15	94	5.8	B	Inv.
Sample 16	94	10	C	Inv.

Inv.: Present Invention

Comp.: Comparative Example

--By employing the film forming apparatus fitted with the shielding blade shown in Fig. 2, preparation was performed under the same conditions as for Sample 11, and the excellent results shown below were obtained.

Transmittance: 97 percent

Volume resistivity: $1.5 \times 10^{-4} \Omega \cdot \text{cm}^3$.

Etching property: A

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